# Procedural Review Voting Sheet 2015 Cycle 1

REGION: China COMMITTEE: PV EVENT: SEMI China PV Standard TC Spring Meeting 2015 DATE OF MEETING: 2015/3/17 PLACE OF MEETING: Kerry Hotel, Shanghai, China COMMITTEE CO-CHAIRS: Guangchun Zhang/ CSI, Jun Liu/CESI SEMI STAFF: Kris Shen A&R Voter: Name/Company Date: 200X/MM/DD

### I. Document Number & Title

5727	Document Title New Standard: Test Method for the Etch Rate of a Crystalline Silicon Wafer by Determining the Weight
	Loss

#### II. Tally (Staff to fill in)

#### Voting Tally: As-cast tally after close of voting period

A minimum of 60% of the voting interests that have voting members within the technical committee must return votes. (Regulations  $\P$  9.6.1)

	Return	Distribution Return Rate
Yellow	93	$\div$ 154 = 60.4% >=60%
Lilac & Others	83	
Total Vote	176	
Reject	0	
Accept	41	]

A&R	Not approved
	Reason:

## III. Rejects

There was no reject submitted.

### **IV. Comments**

Comment 1

<u> </u>		men					
C	F		renced ction	*TF/Committee to fill in if necessary			
omi		Fr	om	Vargas-Beranl,Rafael (ITSdl)			
Comment		Comment		In subsection 2.3, space between 'time' and '.' must be omitted. In addition, writing of introductory paragraph of the section 5 must be verified.			
	[	Discu	ussion	None			
	х	The	The committee agreed to do one of the following actions.				
	^	*No	o motion i	is required in this step.			
			No furthe	er action was taken by the committee.			
			Refer to	the task force for more consideration.			
			New Bus	siness			
		Х	Other				
	Editorial Change						
7			Case 1:	No vote in this section :			
Actio			To be in	cluded and voted on in § 5. Summary of Editorial Changes.			
ר ח pr			Case 2:	Voted in this section :			
Action proposed		Х	Original "TO" fie	section number and at least one full sentence are required in "FROM" and elds.			
a				Section 2.3 Idard specifies the corrosion time.			
		1		ction 2.3 Idard specifies the corrosion time.			
			Justific	ation (If necessary)			
				Section 5.1 the appropriate acid solution contact with silicon material samples for chemical etch,			
		2		<b>tion 5.1</b> (se the appropriate acid solution contact with silicon material samples for chemical etch,			
			Justific	ation (If necessary)			

Motion by/2nd		nd	Fengxia Sun (Yingli)/Tongrong Zhao (JYT)
Vote			30-0 Motion passed
A&R		No	ot approved
Adit	Re	Reason:	

#### Comment 2

	F		renced ction	*TF/Committee to fill in if necessary		
ğ		Fr	om	Gan Yang (Harbin Institute of Technology)		
Comment		Comment		Strongly recommend polishing English carefully		
Ĩ	[	Discu	ussion	None		
	v	The	e commit	tee agreed to do one of the following actions.		
	Х	*No	motion i	is required in this step.		
			No furthe	er action was taken by the committee.		
				the task force for more consideration.		
			New Bus	siness		
	ľ	Х	Other			
	m					
	Editorial Change					
	rial					
	Cha					
	ang					
1	æ					
\ctic			Case 1:	No vote in this section :		
Action proposed			To be in	cluded and voted on in <u>§ 5. Summary of Editorial Changes</u> .		
opo	İ		Case 2:	Voted in this section :		
sed		Х	Original "TO" fie	section number and at least one full sentence are required in "FROM" and elds.		
				Section 4.1.1 ne <mark>S</mark> ilicon <mark>W</mark> afer <mark>E</mark> tch		
		1		e <mark>tion 4.1.1</mark> ne <mark>s</mark> ilicon <mark>w</mark> afer <mark>e</mark> tch		
			Justific	ation (If necessary)		
				Section 4.1.2 olation <mark>E</mark> tch		
		2		t <b>ion 4.1.2</b> Dation <mark>e</mark> tch		
			Justific	ation (If necessary)		
		3	FROM: Etch Ra	Section 4.1.3 ate		

		To: Section 4.1.3 etch rate							
	Justif	Justification (If necessary)							
	<mark>D</mark> eptl	<b>//: Section 4.1.4</b> n of <mark>E</mark> tch							
4	To: Section 4.1.4 depth of etch								
	Justi	fication (If necessary)							
Motion b	by/2nd	Fengxia Sun (Yingli)/Tongrong Zhao (JYT)							
Vot	e	30-0 Motion passed							
A&R	No	ot approved							
Adr	Reason:								

#### **V. Summary of Editorial Changes**

Note: Original section number and at least one full sentence are required in "FROM" and "TO" fields.

See editorial changes above.

### **VI. Approval Conditions Check**

**APPROVAL CONDITION 1:** All negatives have been discussed and were withdrawn, found not related, or not persuasive. (Regulations  $\P$  9.6.2)

**APPROVAL CONDITION 2:** At least 90% of the sum of the valid accept and reject votes must be accept. (Regulations  $\P$  9.6.3)

Note: if both approval conditions are not satisfied, the document fails.

		Accepts	(Accepts + Valid		
Approval Rate	=	41	/ 41	= 100.0%	>=90%

A&R		Not approved
	Re	ason:

	36	e 3	§ 14 of the Regulations for further information					
z	x	This is not a Safety Document: when all safety-related information is removed, the document still technically sound and complete.						
Motion:					y Document: when all safety-related information is removed, the document is not and and complete.			
					ecklist (Regulations ¶ 14.3) is complete and has been included with the document the balloting process.			
N	<b>/</b> loti	ion b	y/2r	nd by	Fengxia Sun (Yingli)/Tongrong Zhao (JYT)			
	D	)iscu	Issio	on	None			
Vote 30-0 Motion passed					30-0 Motion passed			
	A&F	Not approved						
		N I	Re	ason:				

### VIII. Intellectual Property Check

	Note:	This b	allot may	<b>Property Check</b> be all or part of a Standard or Safety Guideline. This IP check applies or Safety Guideline. See § 15 of the Regulations for further information				
Х		ne meeting chair asked those present in person or by electronic link, if they were aware of any otentially material patented technology or copyrighted items* in the Standard or Guideline.						
	Х		otentially n nown	naterial patented technology or copyrighted items <b>GO TO SECTION IX</b>				
	Potentially material patented technology or copyrighted items are known but a Letter of Assurance (LOA) or copyright release for such material has been obtained or presented to the committee.							
		сору		erial patented technology or copyrighted items are known but an LOA or se for some of the material(s) has NOT been obtained or presented to the				
	M		Ask ISC f	or special permission to publish				
	MOTION		Quit activ	ty				
	Ň		Wait for L	OA for patented technology or release of copyrighted items.				
	Мо	tion by	y/2 <sup>nd</sup> by					
	0	Discus	sion					
		Vot	e					
	F	inal A	ction	Motion Passed				
				Motion Failed				
•	&R		Not appro	ved				
A	an	Reas	son:					

\* Note: Such potentially material patented technology or copyrighted items might have become known since the Standard or Safety Guideline was last reviewed, or might become relevant due to this ballot.

### IX. Action for this document

		This document passed committee review as balloted and will be forwarded to the A&R procedural review.					
This document passed committee review with editorial changes and will be forwa A&R for procedural review.							
		Th	is do	cum	ent failed committee review and will be returned to the task force for rework.		
		Th	is do	cum	ent failed committee review and work will be discontinued.		
r	Motion by/2nd by			b	Fengxia Sun (Yingli)/Tongrong Zhao (JYT)		
	Dis	cus	sion		None		
		Vote	e		30-0 Motion passed		
	Fina		ction		X Motion passed		
	1 1110				Motion failed		
	<b>V 8 E</b>	&R		Ар	proved		
	AQL			No	t approved		

Reason.
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